

Characterization of passive CMOS strip detectors

Marta Baselga, Leena Diehl, Ingrid-Maria Gregor, Marc Hauser, Tomasz Hemperek, **Jan Cedric Hönig**, Fabian Lex, Ulrich Parzefall, Arturo Rodriguez Rodriguez, Surabhi Sharma, Dennis Sperlich, Tianyang Wang, Liv Wiik-Fuchs

Albert-Ludwigs-Universität Freiburg



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CMOS strip - detectors



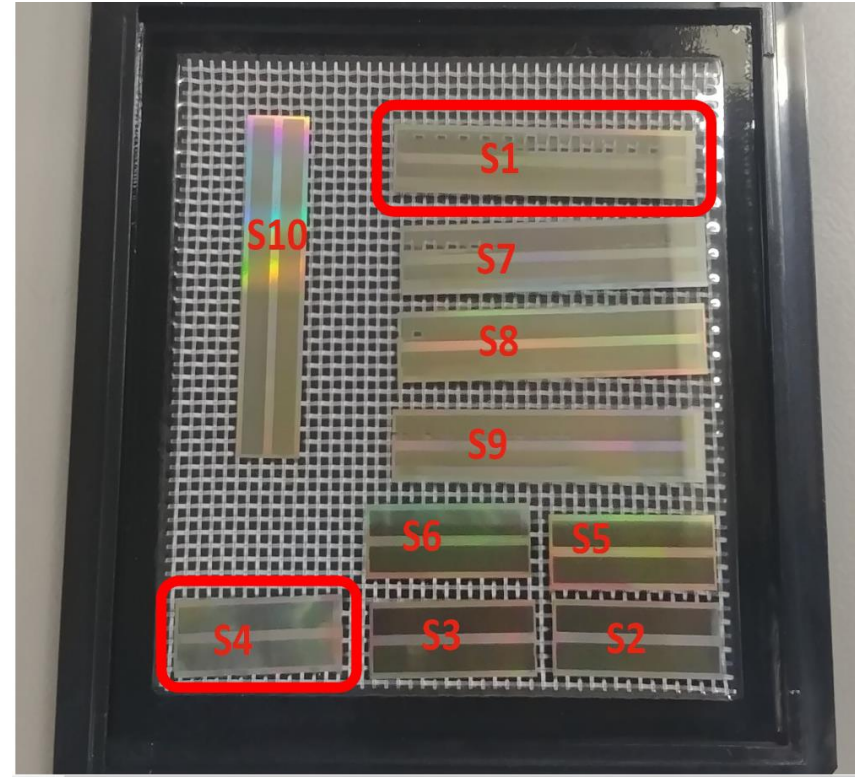
First stitched strip sensors produced on 8" wafer by a commercial high volume foundry.

LFA150:

- L-Foundry 150 nm process (deep N-well/P-well)
- Up to 7 metal layers
- Resistivity of wafer: $>2000 \Omega \cdot \text{cm}$
- Float-Zone silicon

Frontside process: Reticle stitching for large sensors

Two sensor lengths 2 cm and 4 cm.



CMOS strip - details

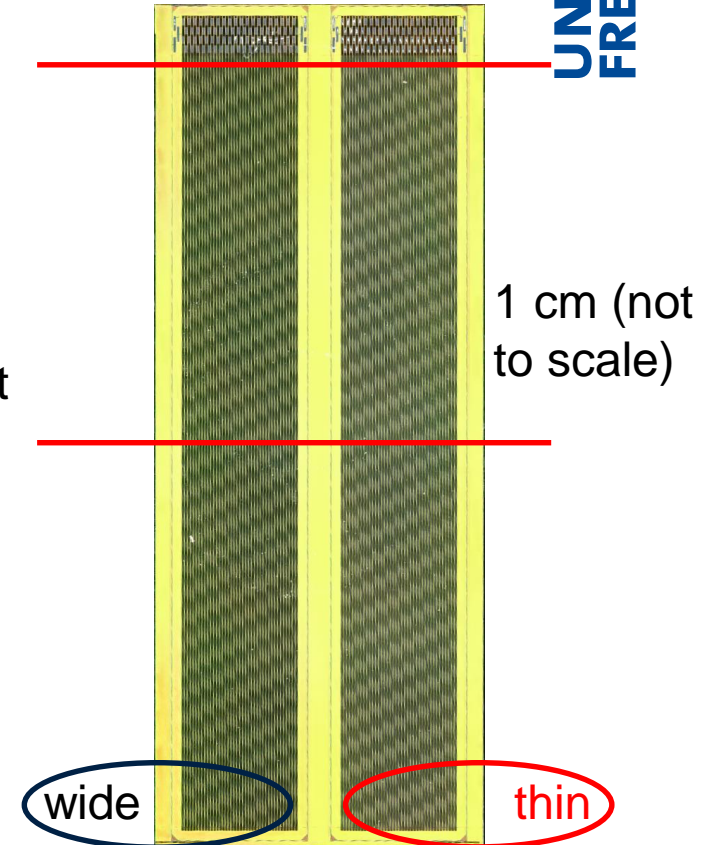


Two sensor lengths 2 cm and 4 cm.

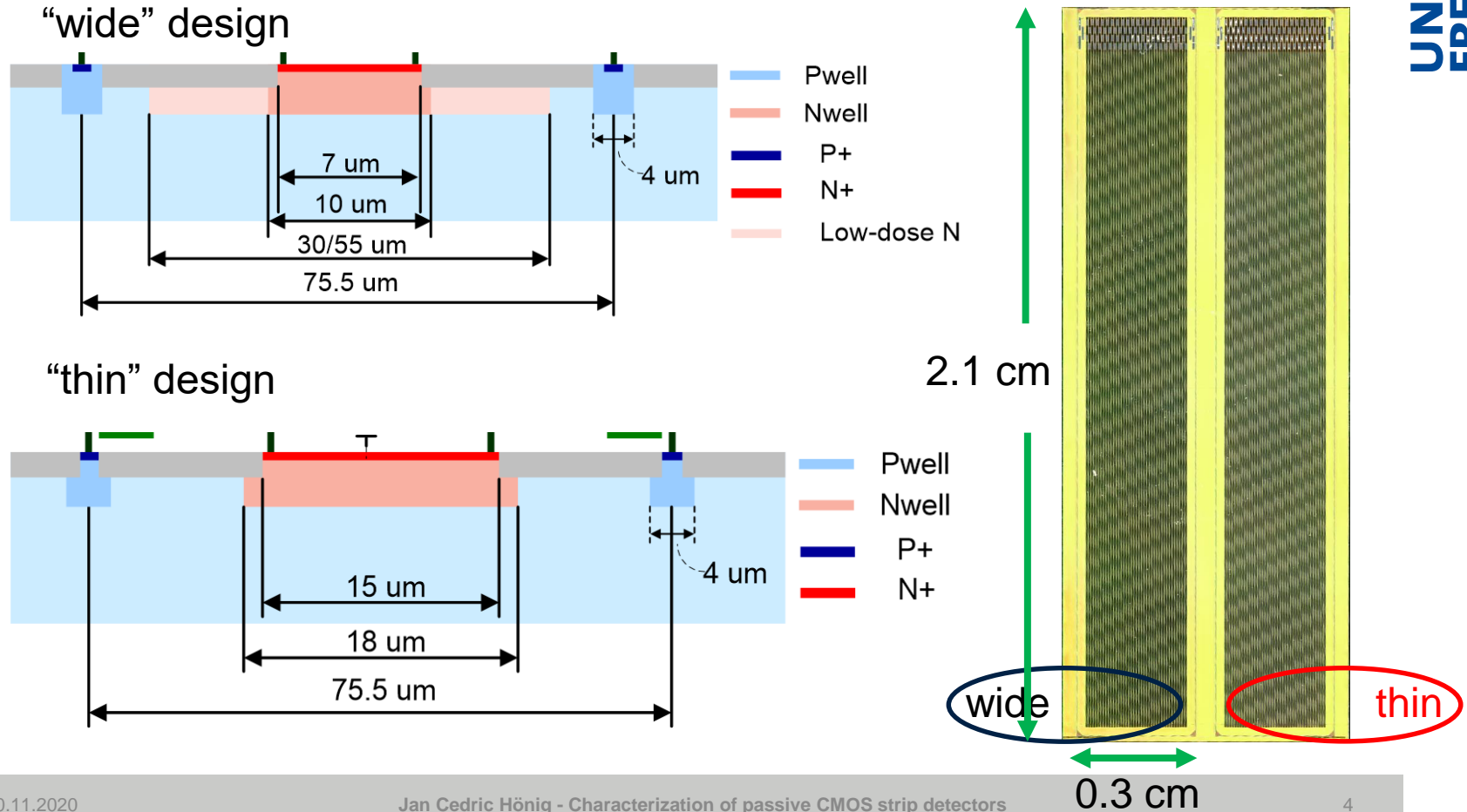
The sensors contain a stich every 1 cm along their length.

Two different sensor flavours divided in left and right half of the sensor.

The left half (“wide”) is further divided featuring two different implant lengths.



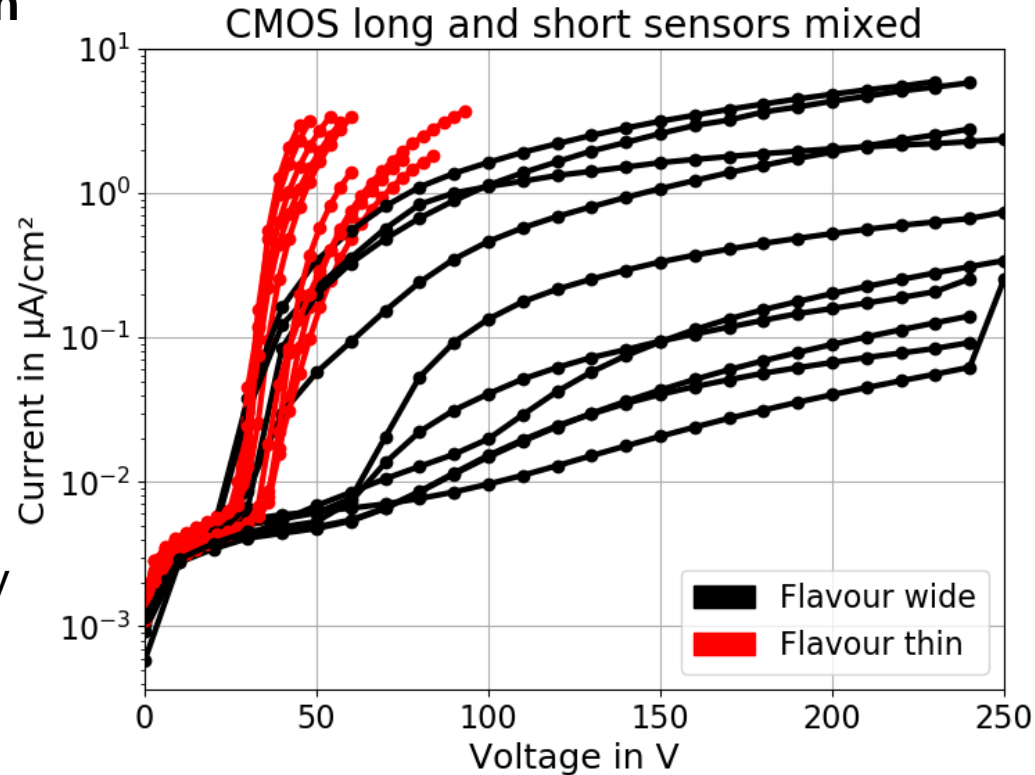
CMOS strip - implants



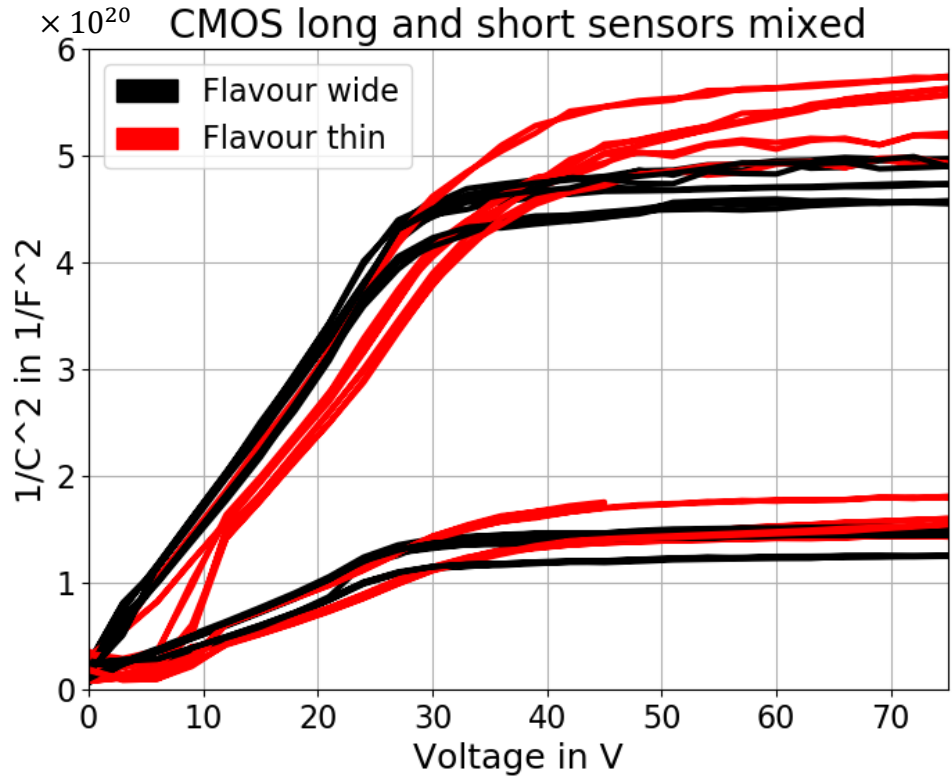
No backside passivation

The left half (“wide”) shows lower power consumption in the majority of sensors.

The right half (“thin”) shows strong increase in leakage current at low voltages, could potentially be problematic after irradiation.



CV results



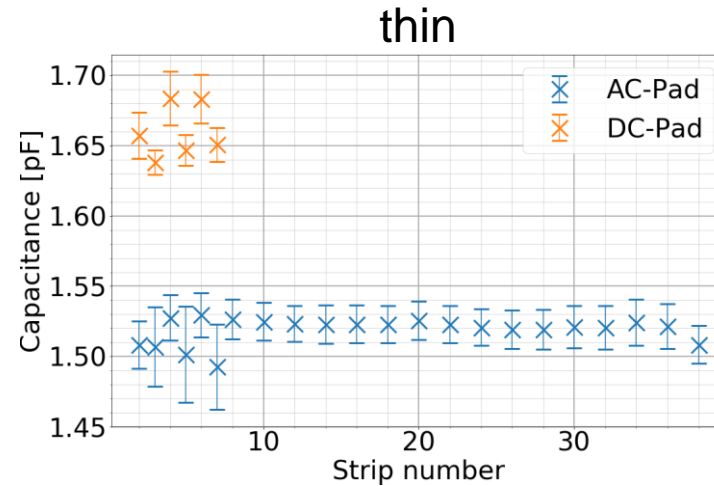
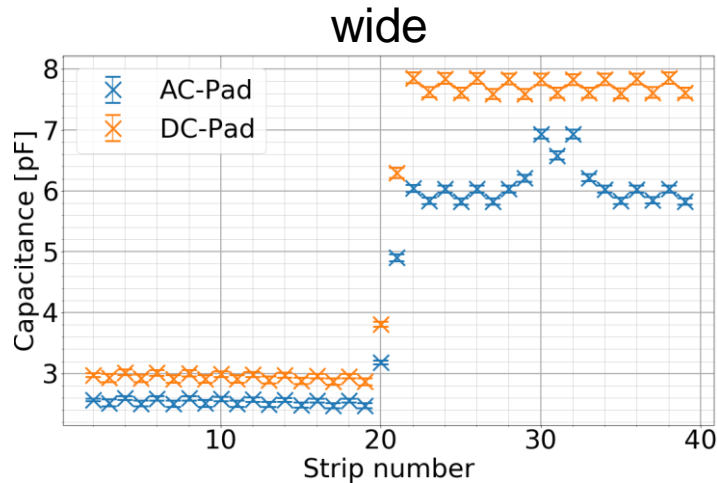
4 cm
sensors

Both strip designs
deplete around 25 – 40 V

2 cm
sensors

“thin” design has smaller
implant < 20 μm with
76 μm pitch

Interstrip capacitance measurement



On the left two different strip designs visible.

No effect from stitching visible.

Sensor	Capacity/Length [fF/mm]
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“wide” left	62 ± 0.2
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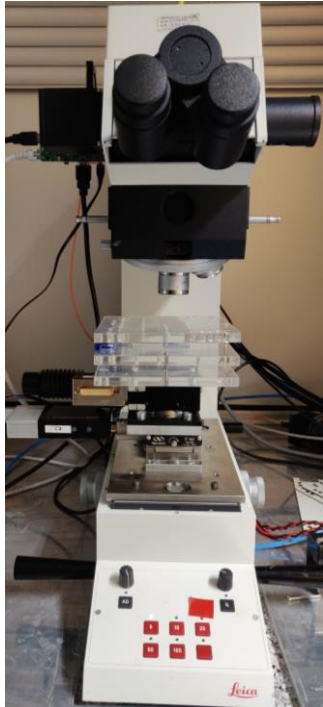
“wide” right	144 ± 0.4
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“thin”	37 ± 0.1
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Hamamatsu	65 ± 0.6
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Laser measurements

AliBaVa setup

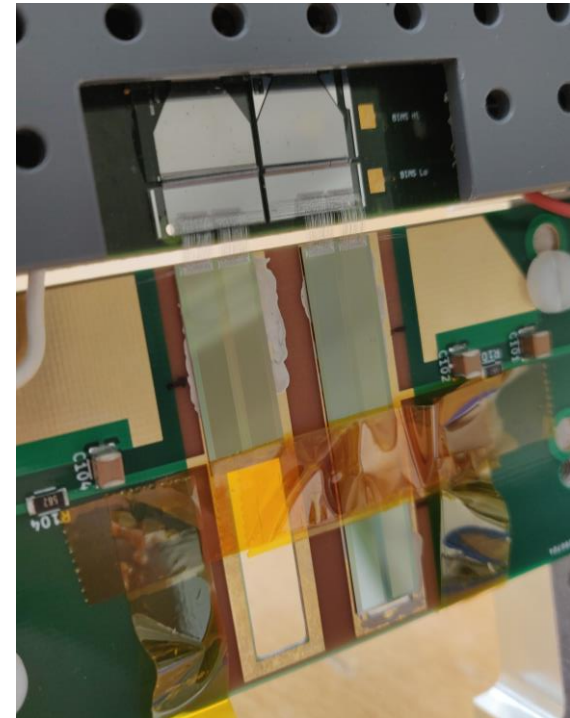


AliBaVa laser
setup

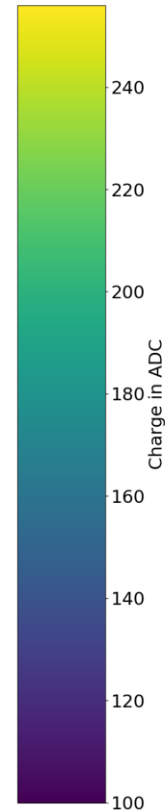
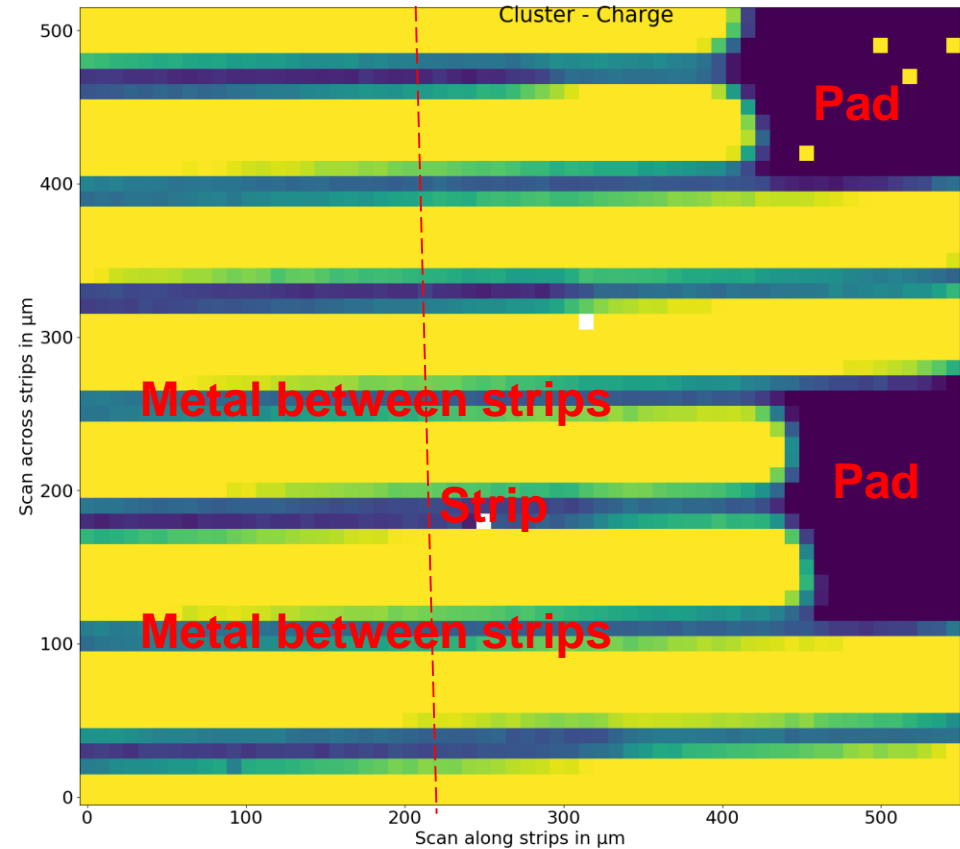
AliBaVa laser setup consists of a fibre coupled infrared laser and two motorstages which move the sample with μm precision.

Sensors are placed on a board with a large cut-out to make the back of the sensor accessible.

Signal is sampled.

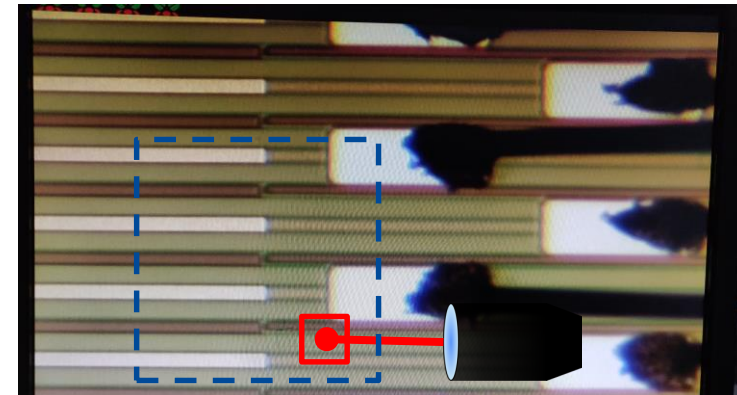


Laser stitch check

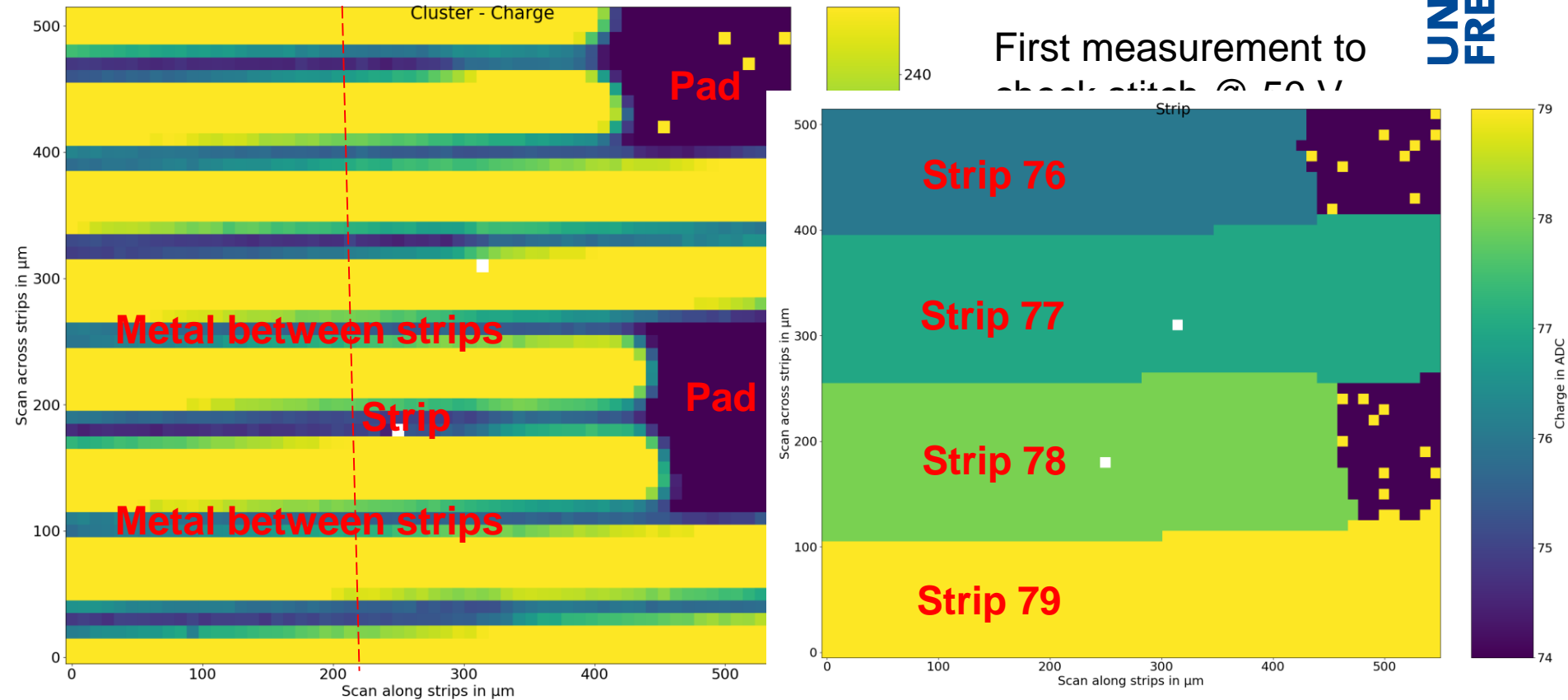


First measurement to check stitch @ 50 V

Due to the metallization (blue horizontal lines): results are only hints



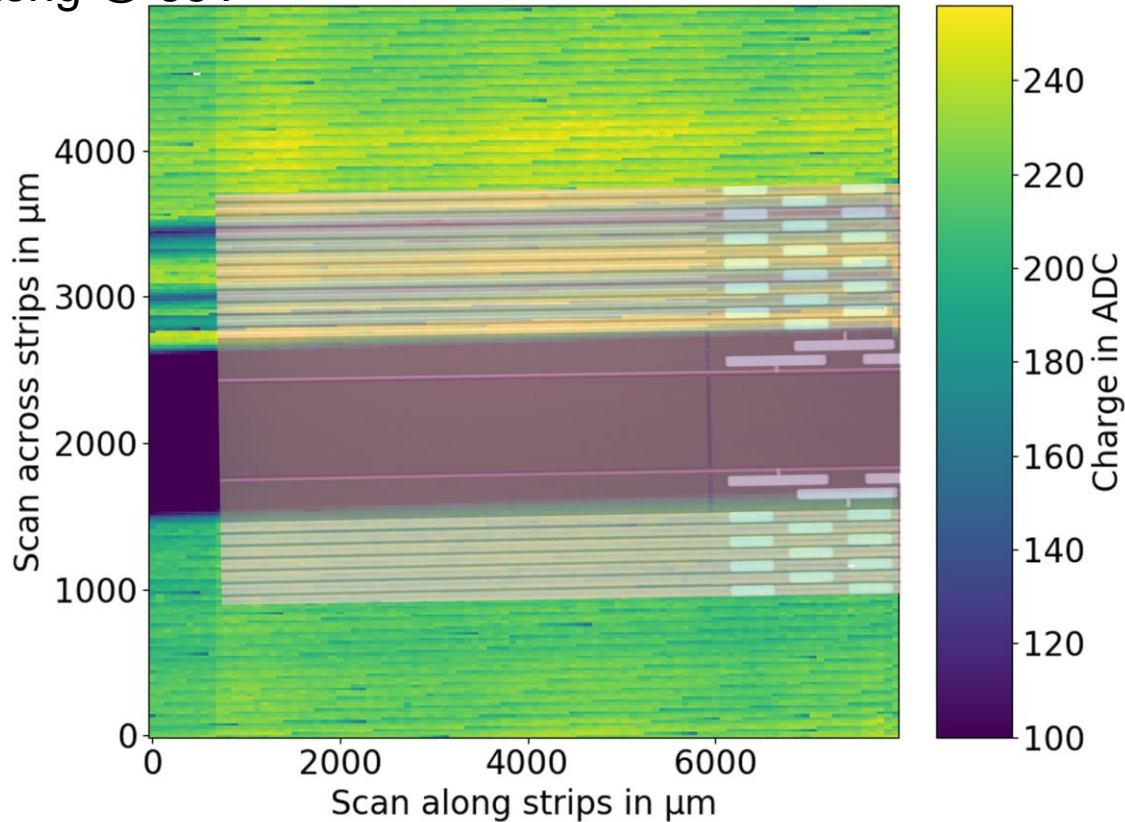
Laser stitch check



Scan for homogeneity



Long @ 35V



Sensor “thin” shows
 228 ± 12 ADC

(these numbers still contain
systematic noise from our
system in the order of 1.8
ADC)

Sensor “wide” shows
 213 ± 8 ADC

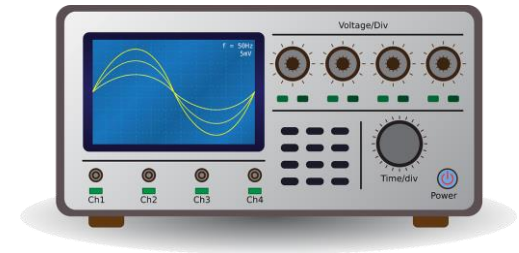
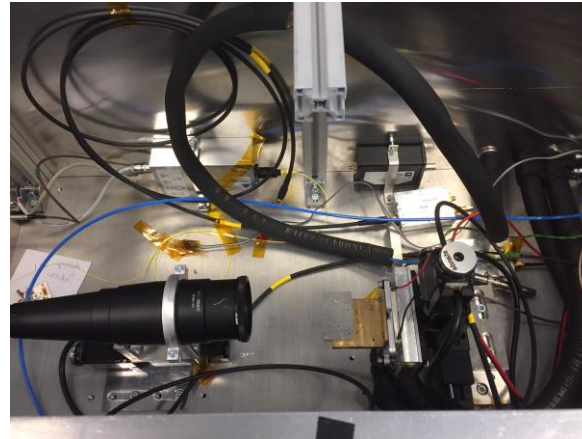
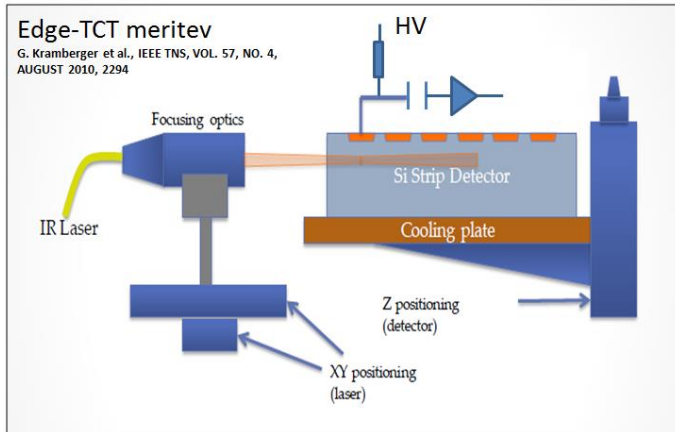


Sensor illuminated
from the back.

TCT technique

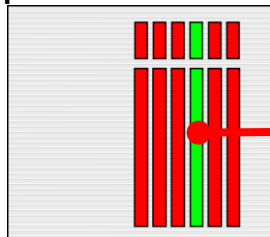


Side view: Particulars **EdgeTCT** setup



Signals are “fully” recorded with an oscilloscope.

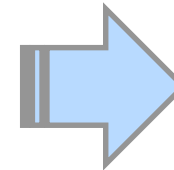
Top view: Sensor



Laser



- Strip - grounded
- Strip - measured

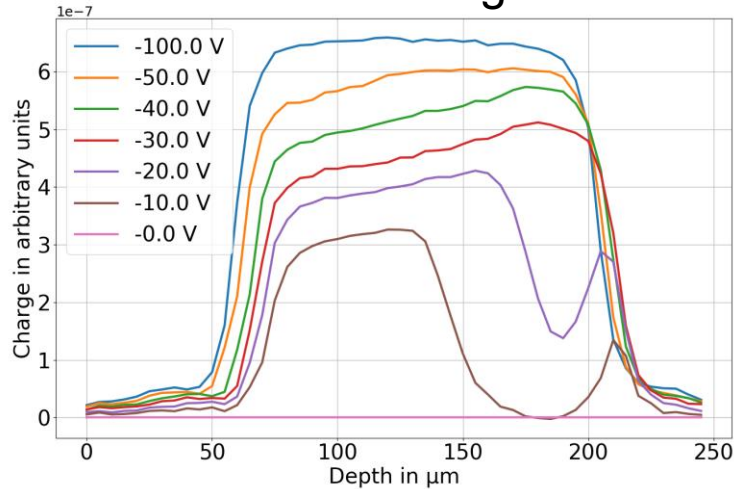


TopTCT – illuminate sensor from top instead of edge.

E-TCT charge collection



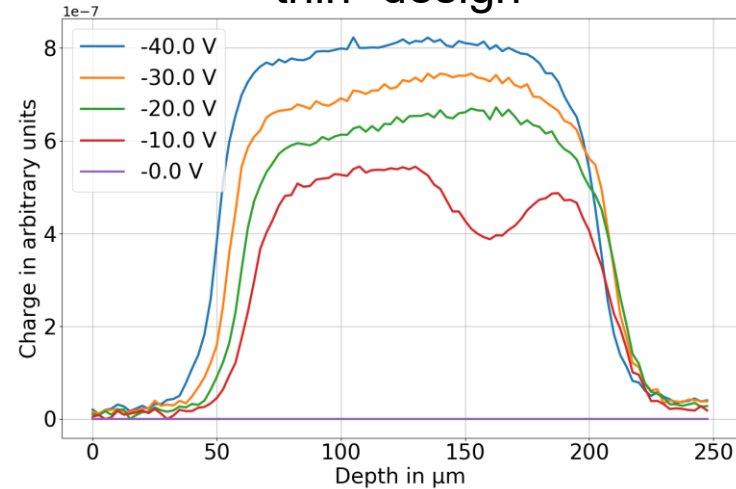
“wide” design



E-field changes shape until around 50 V bias.

Probably connected to backside processing issues.

“thin” design

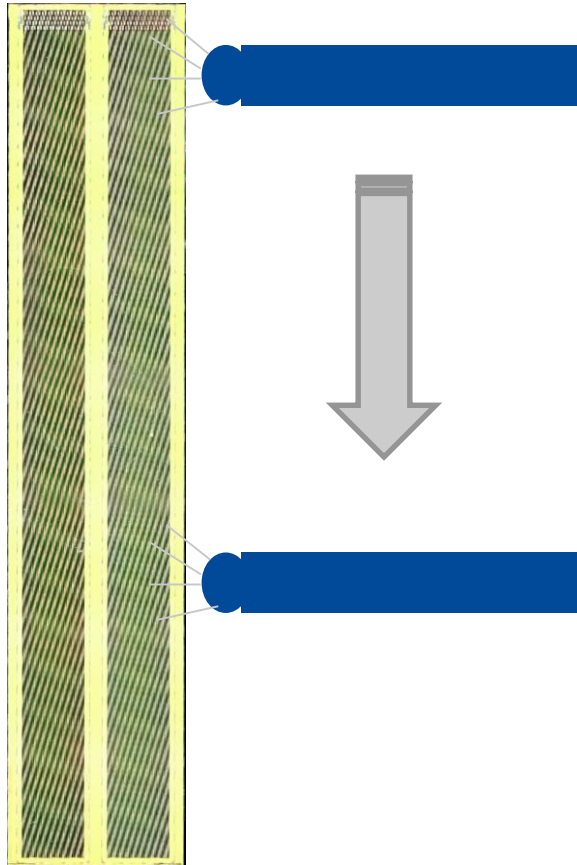


E-field changes shape until around 30 V bias.



Source measurements

Source measurement – the method

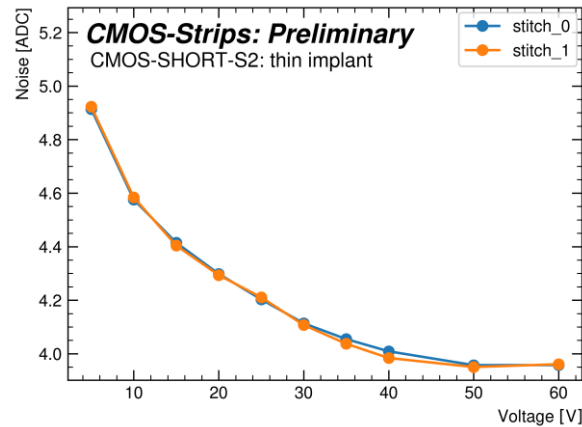
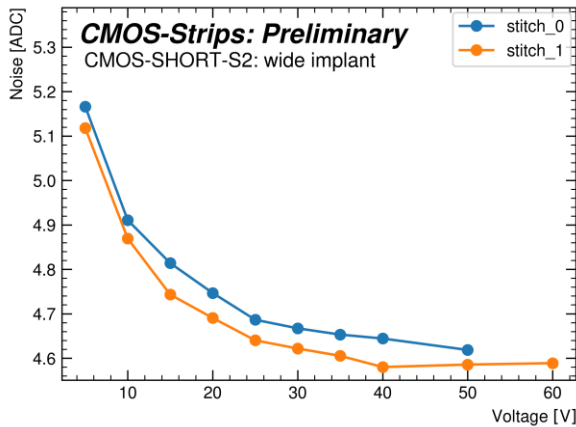
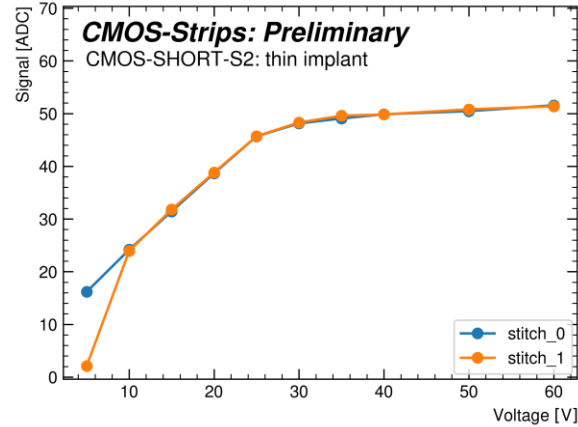
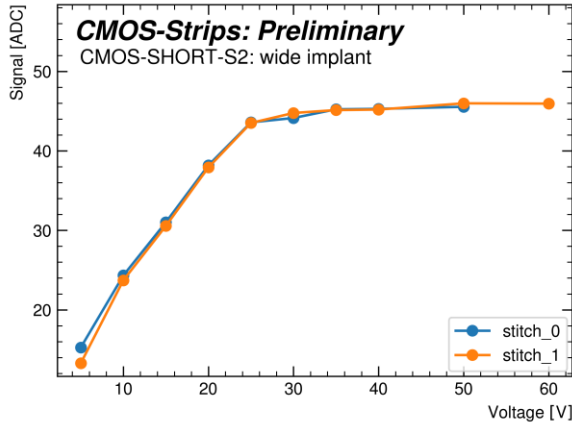


We use the AliBaVa readout system.

Move the source between measurements by 1 cm.

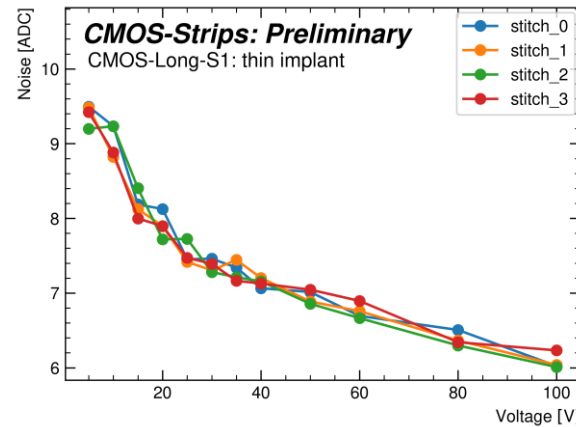
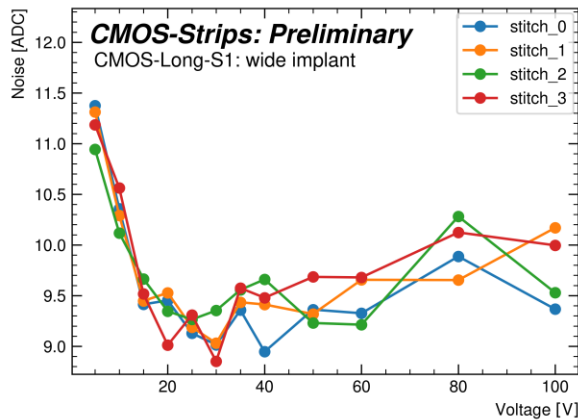
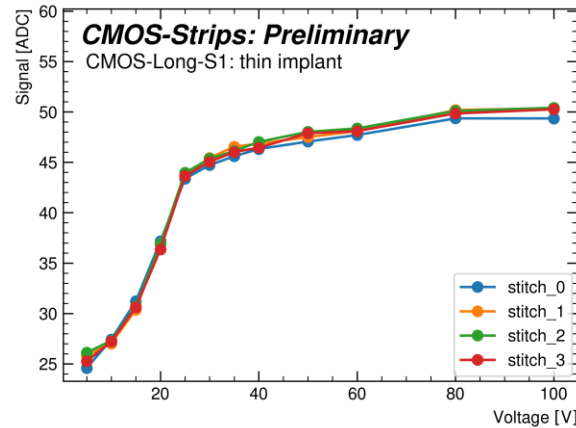
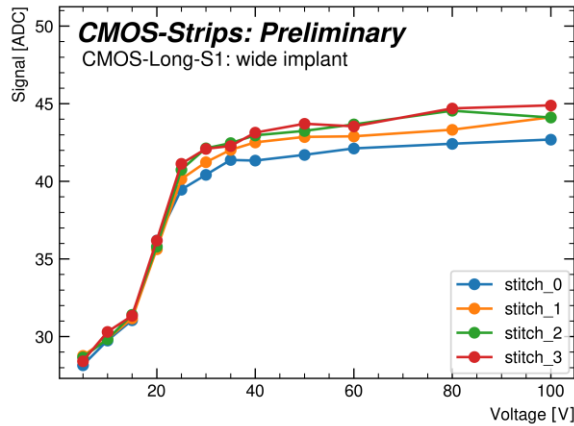
Majority of electrons pass through a different stitch after every move.

Source measurement



No degrading visible along stitches.

Source measurement



No degrading visible along stitches.

Need to understand effect of the 2 different designs used in the “wide” sensor.

Low S/N



Sensor

The “wide” sensor design is better suited to withstand high voltages. Break down for healthy sensors is larger than 250 V.

At low bias voltages (around 50 V), the “thin” sensor design shows better charge collection.

Stitching

No negative effect from stitching could be observed in the measurements conducted so far.

Outlook:

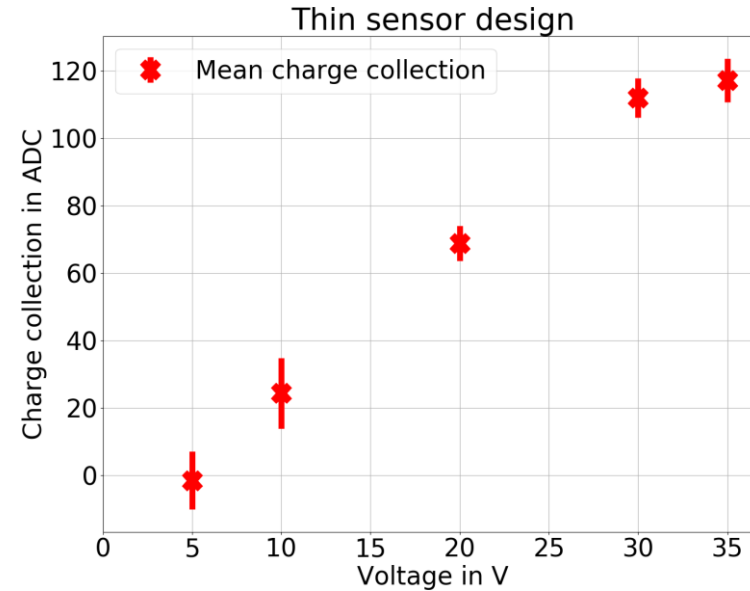
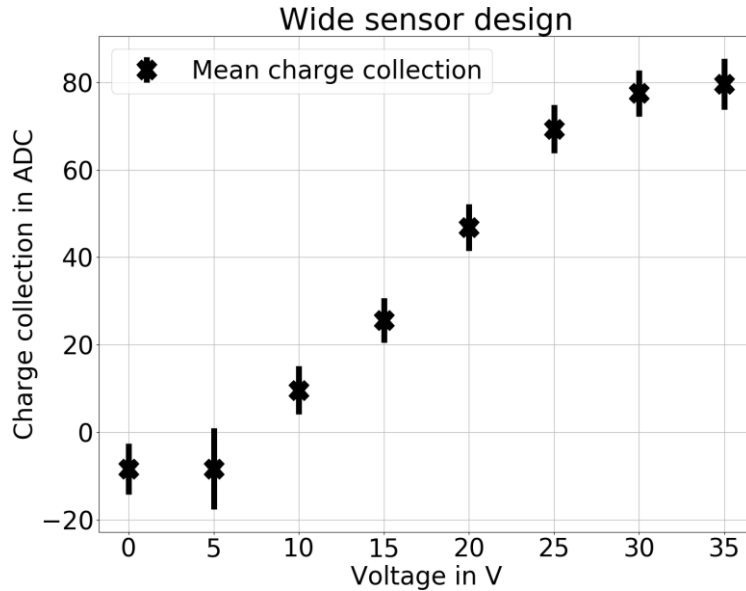
Sensors were measured at the testbeam facility in DESY recently.

Irradiation studies planned.

First batch had backside processing issues, better electrical results expected for the next batch.



Charge collection vs voltage



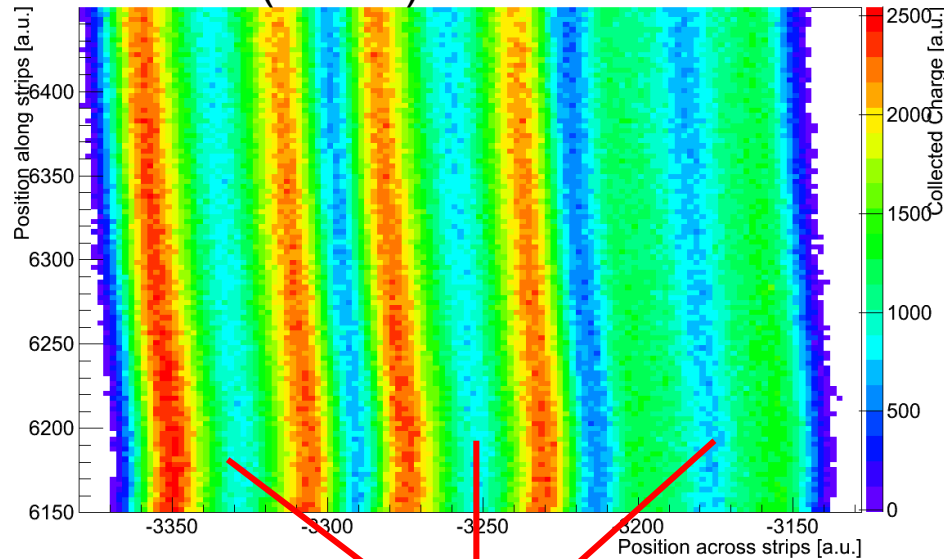
Results from laser measurements.

TopTCT measurement



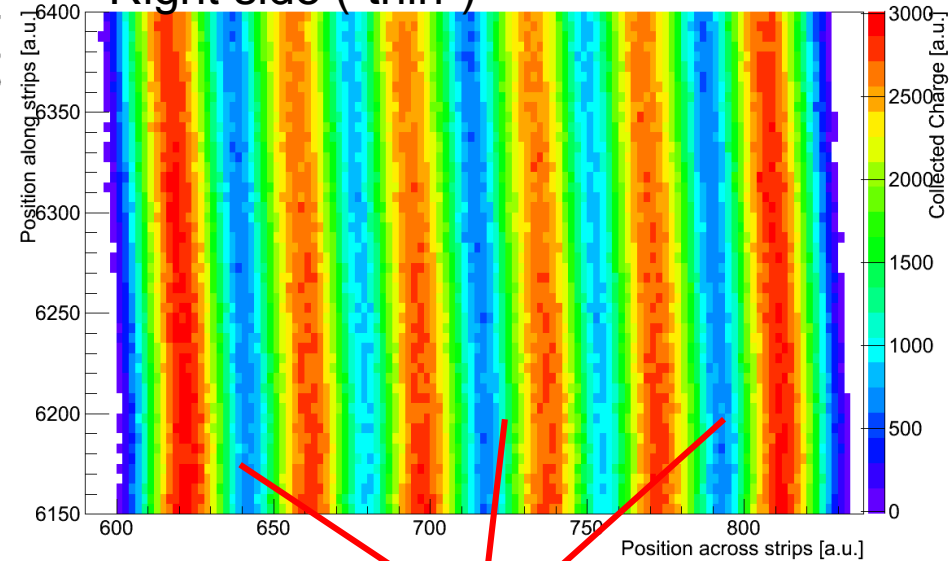
- Left side: Probably one bond lost -> See only the shared charge
- Collected Charge slightly higher for right side of the sensor

Left side (“wide”)



Strips

Right side (“thin”)



Strips